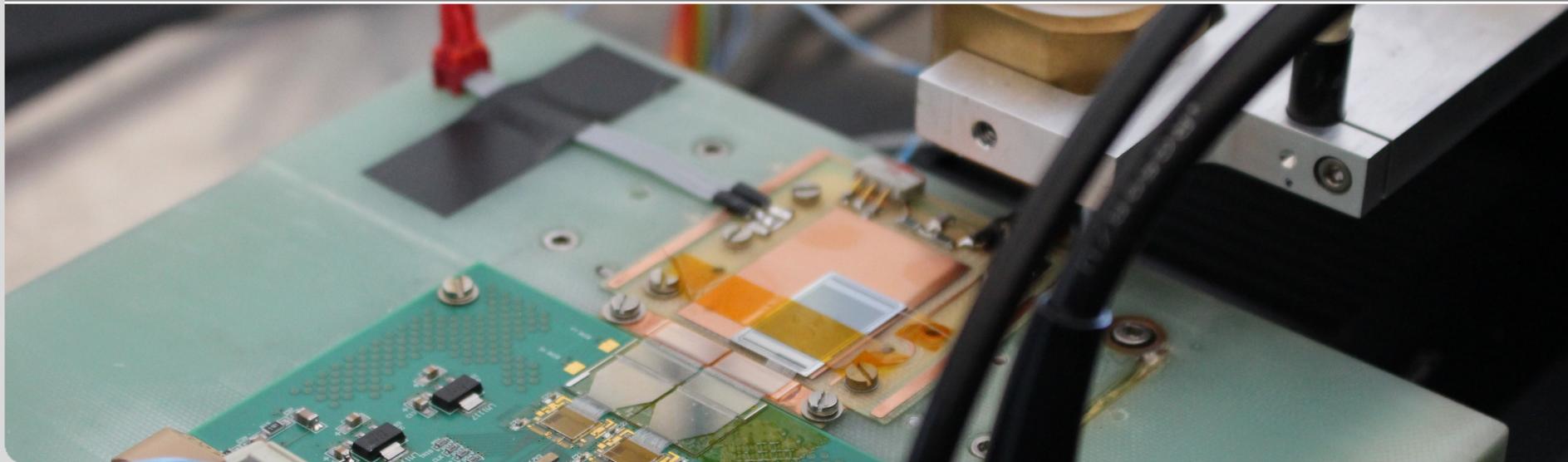


# DPG 2017: Front Side Biasing of Silicon Sensors

Felix Bögelspacher, Alexander Dierlamm, **Marius Metzler**, Thomas Müller, Pia Steck

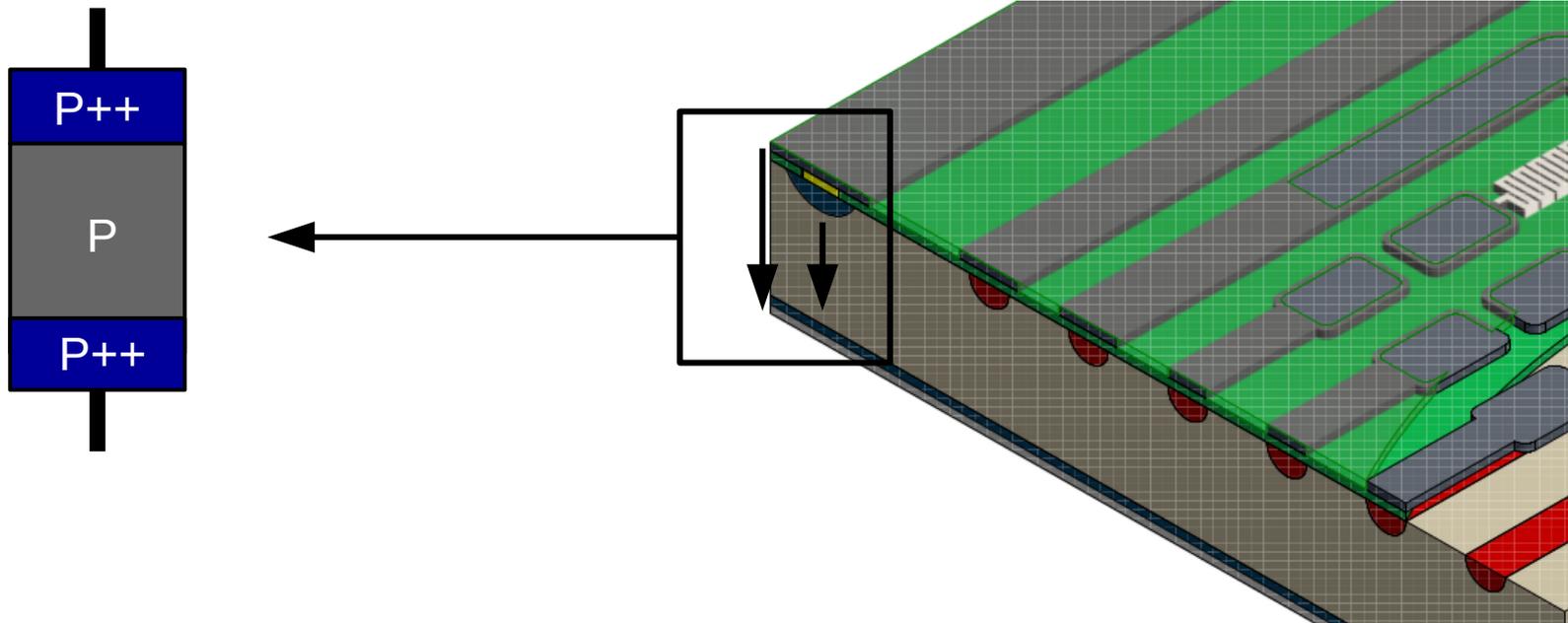
Institut für Experimentelle Kernphysik (IEKP)



# I. Motivation & Working Principle

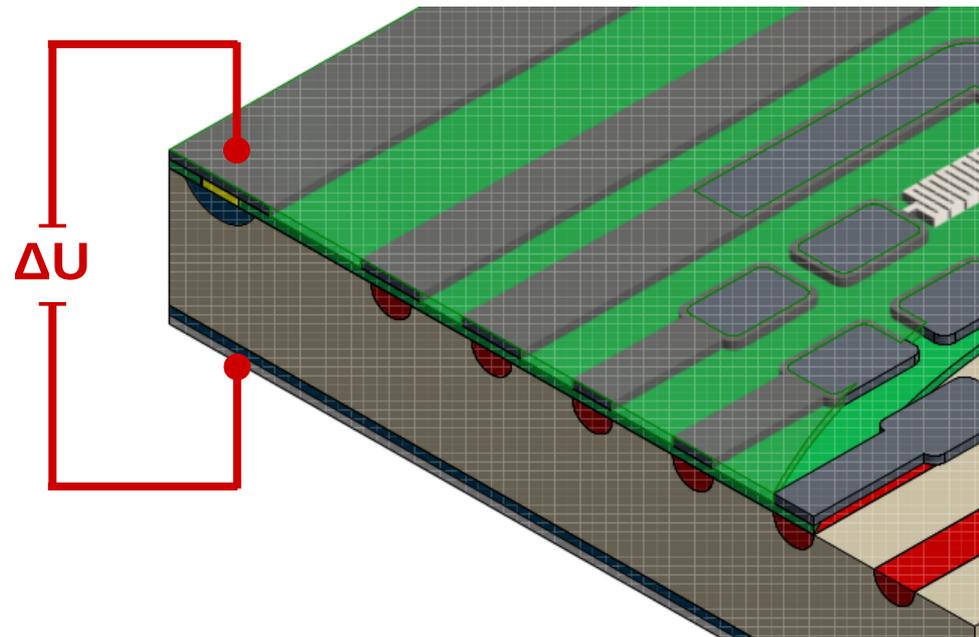
# I. Motivation & Working Principle

- Periphery region between top side and backplane works like a resistor made of different p-doped layers (over-simplified!)



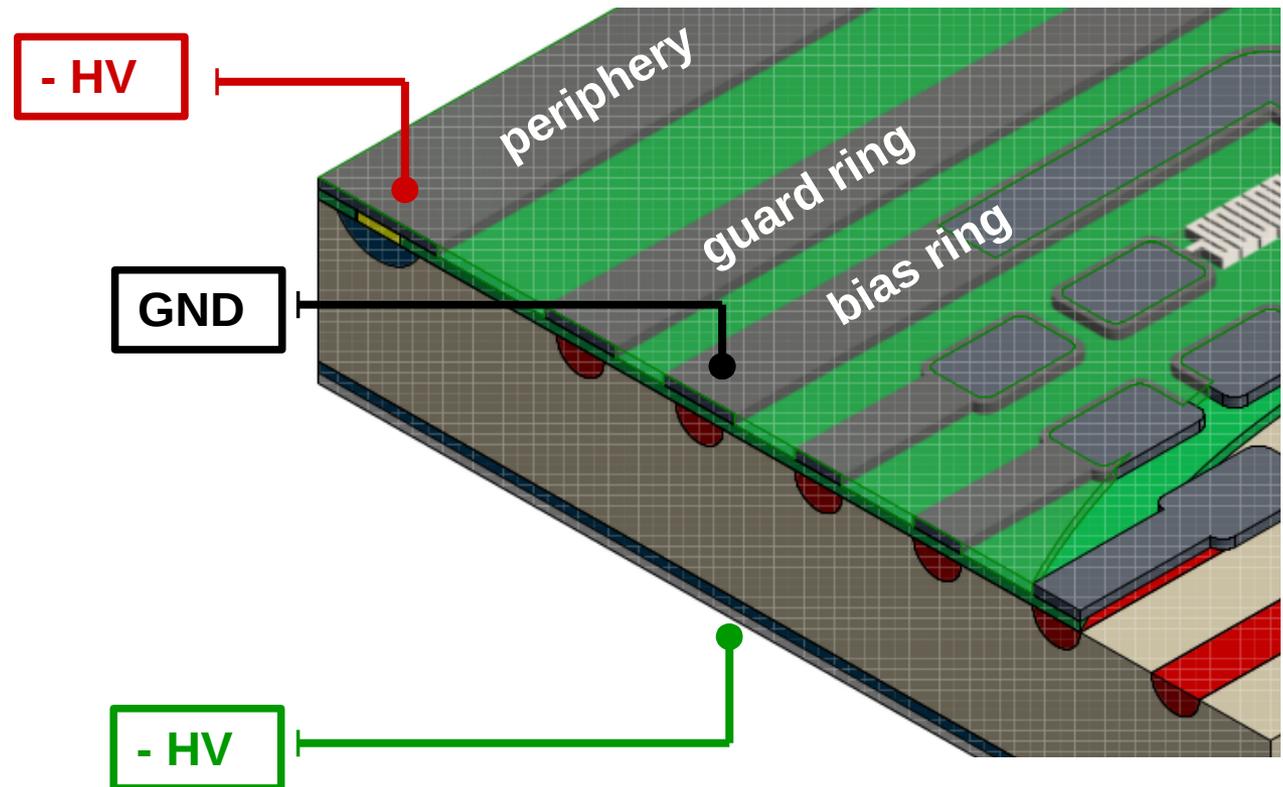
# I. Motivation & Working Principle

- Think of the periphery region between top side and backplane as a resistor made of different p-doped regions (over-simplified!)
- If you set the top side to a certain potential, the backplane is naturally set to a similar potential depending on the resistance of this “resistor”
  - Voltage drop  $\Delta U = I \cdot R_{\text{Edge}}$



# I. Motivation & Working Principle

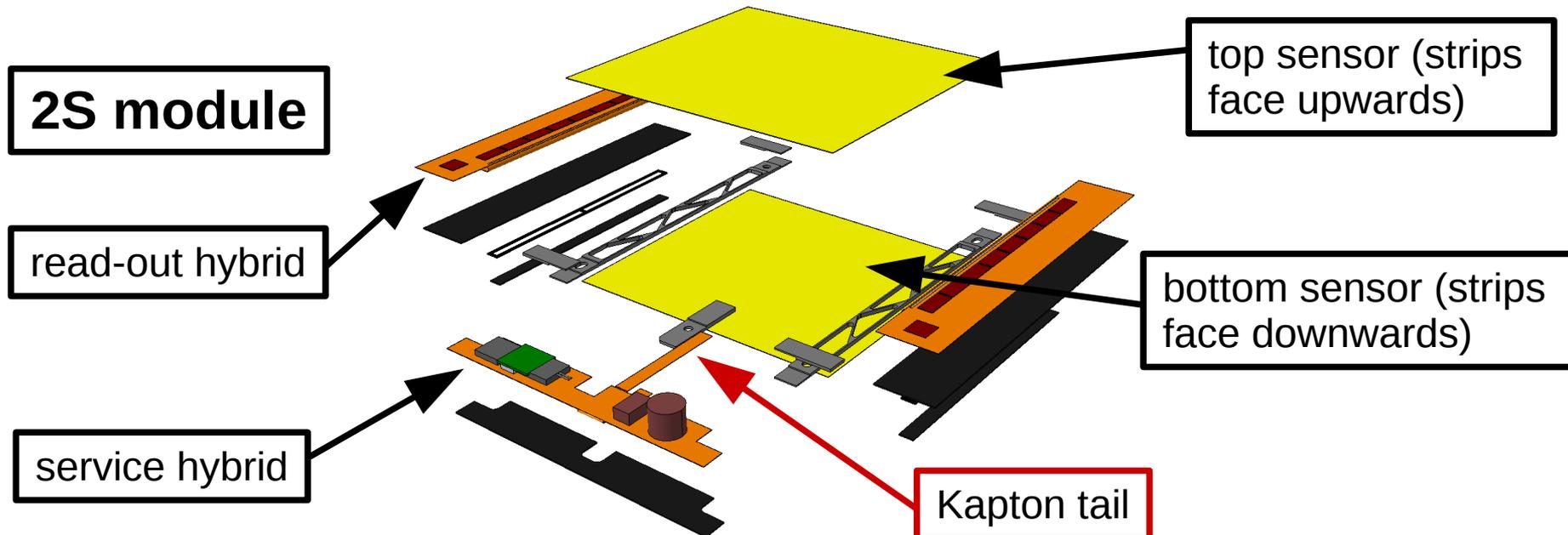
- Normal way of biasing a n-in-p sensor (**back side bias**)
- **Front side bias**

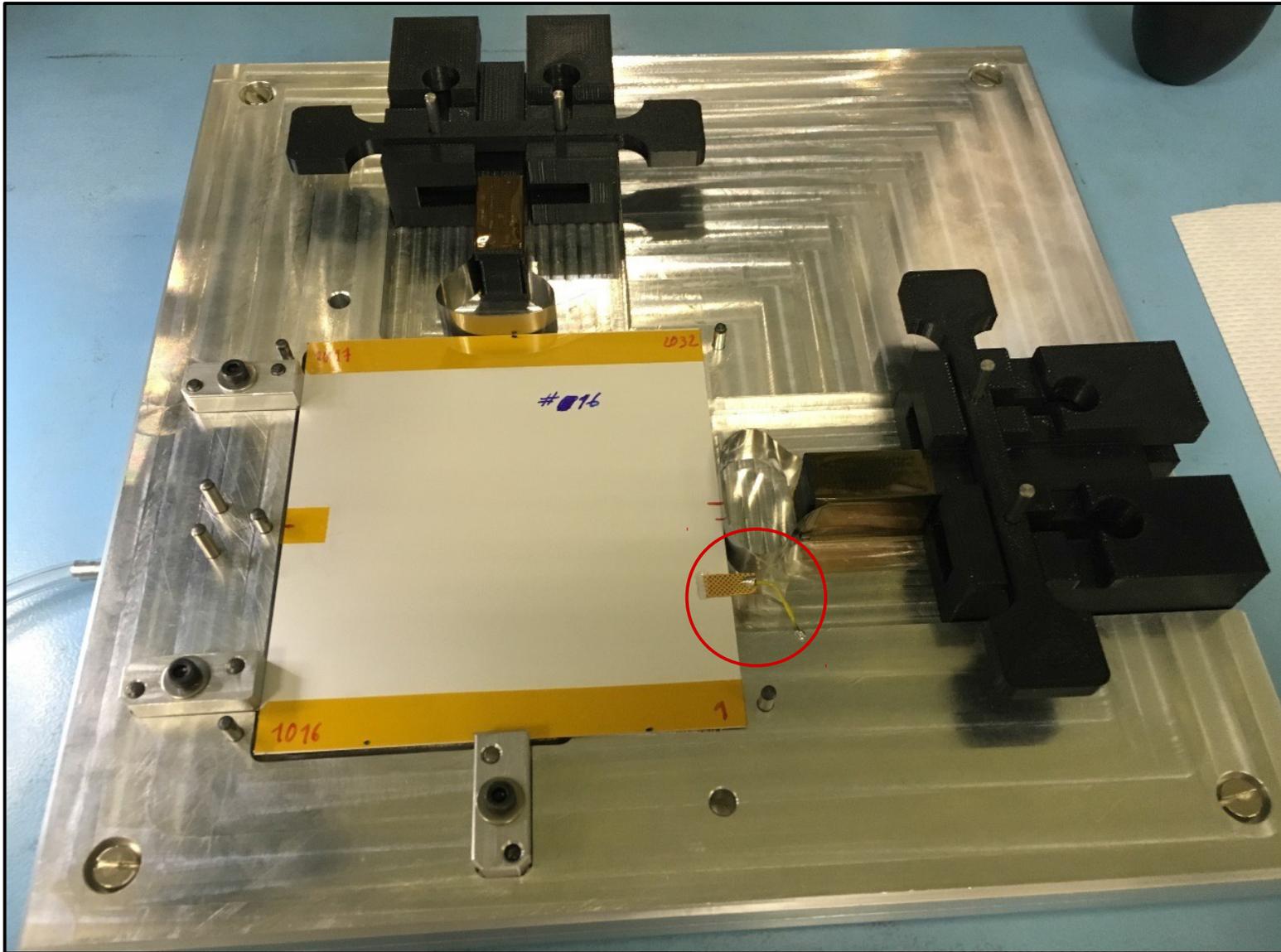


# I. Motivation & Working Principle

■ FSB would facilitate the module assembly because 3 time-consuming working steps would be eliminated:

- 1) ~~Kapton tail attachment~~
- 2) ~~Kapton tail bonding~~
- 3) ~~Kapton tail encapsulation~~





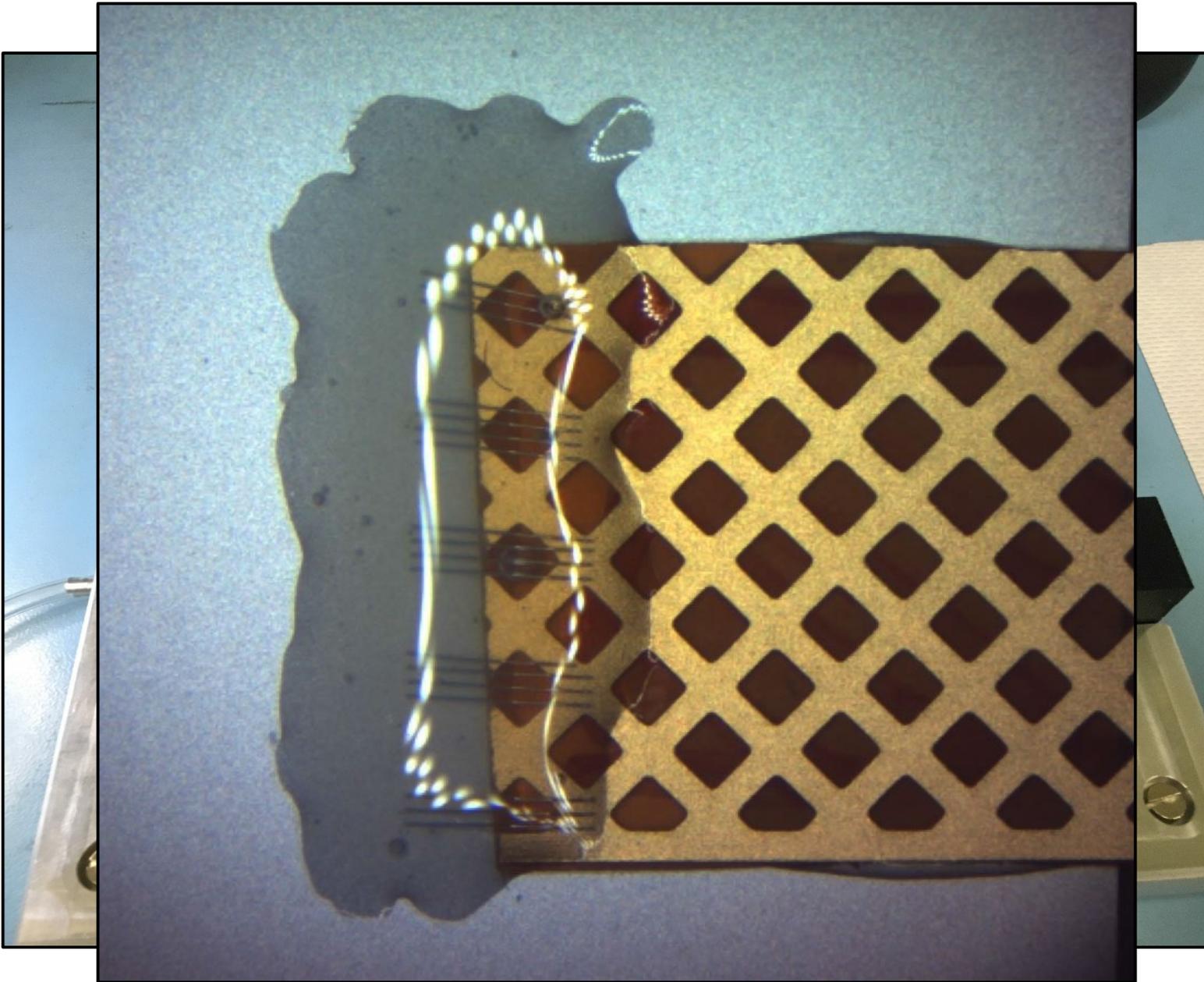
th tail has

ble

nsor (strips  
pwards)

nsor (strips  
wnwards)

Rapton tail



th tail has

ble

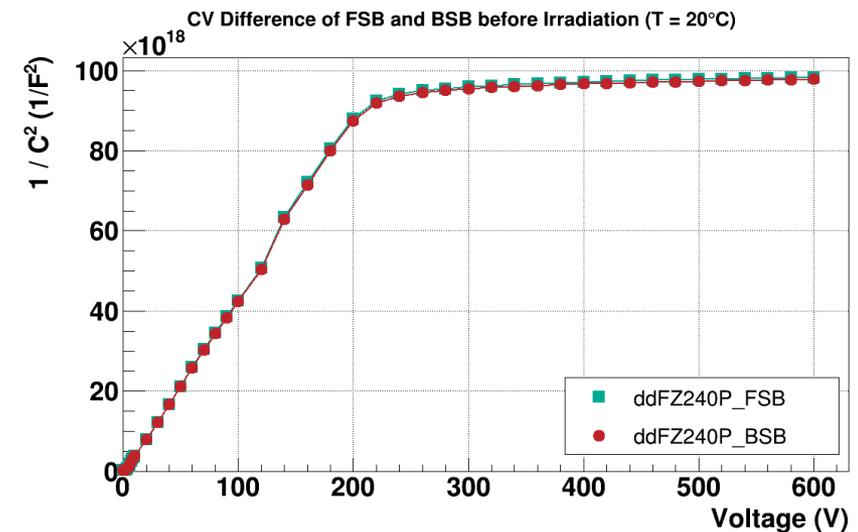
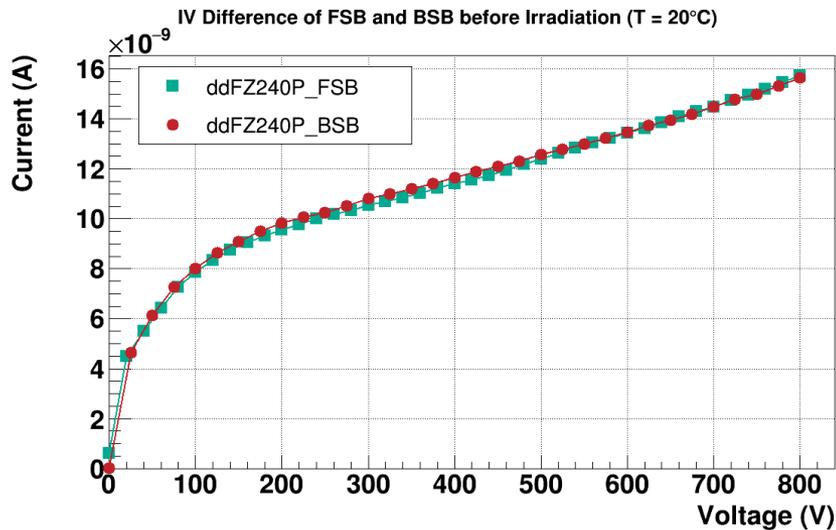
nsor (strips  
pwards)

nsor (strips  
wnwards)

## **II. Evaluation Front-Side-Biased Sensor Parameters**

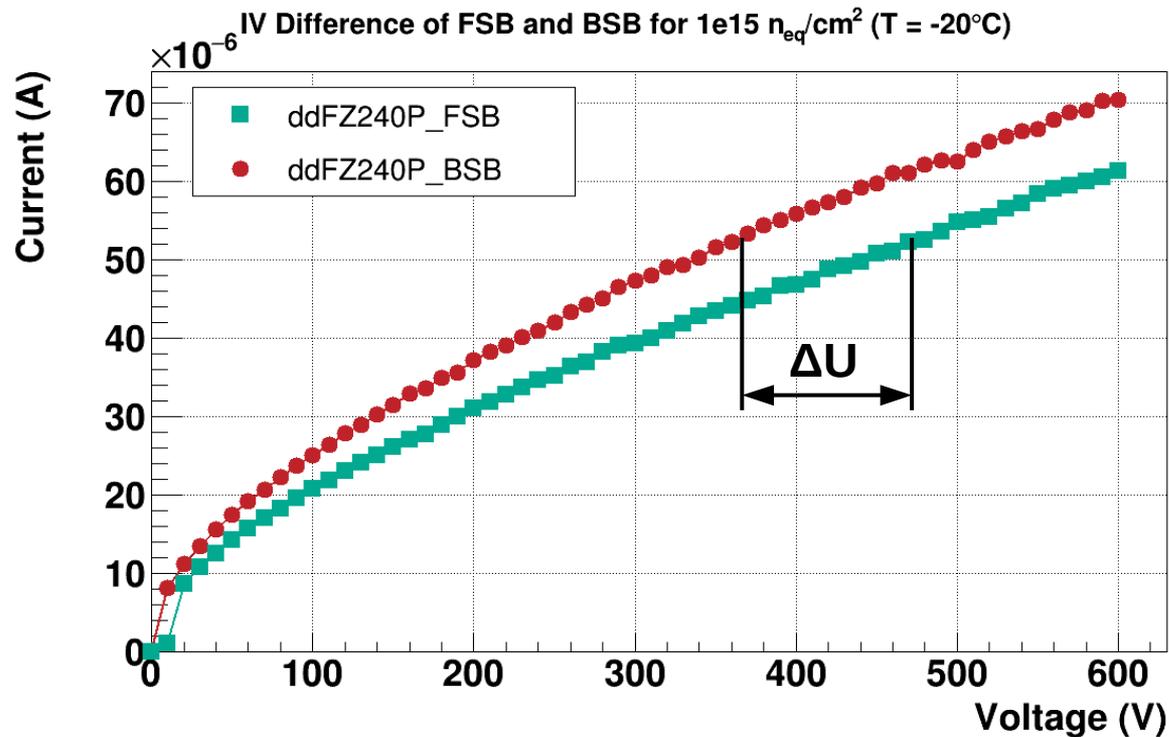
## II. Evaluation of Front-Side-Biased Sensor Parameters

- No significant difference of
  - current-voltage-characteristics (IV)
  - capacitance-voltage-characteristics (CV)
 before irradiation



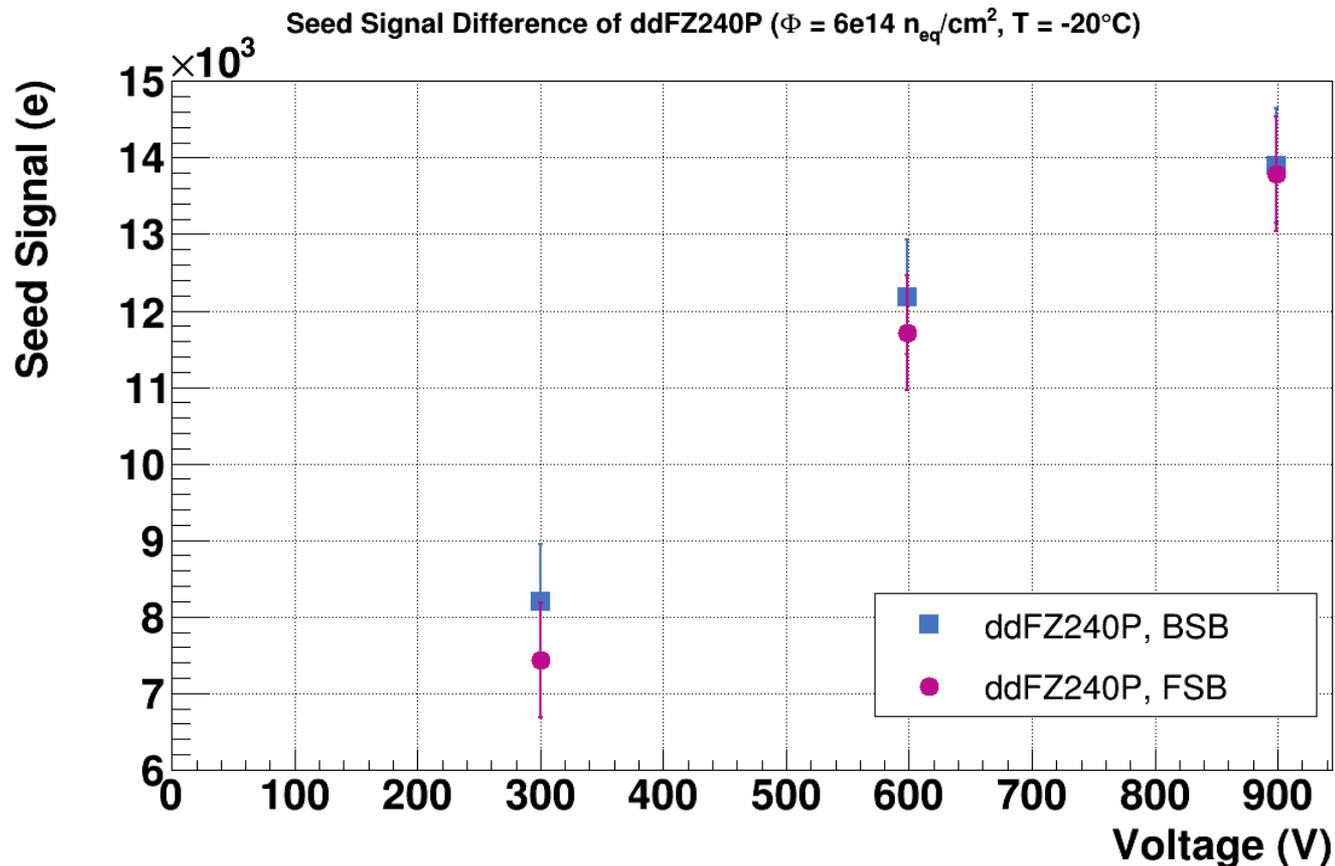
## II. Evaluation of Front-Side-Biased Sensor Parameters

- However:  $\Delta U$  clearly observable for fluences beyond  $6e14 \text{ n}_{\text{eq}}/\text{cm}^2$



## II. Evaluation of Front-Side-Biased Sensor Parameters

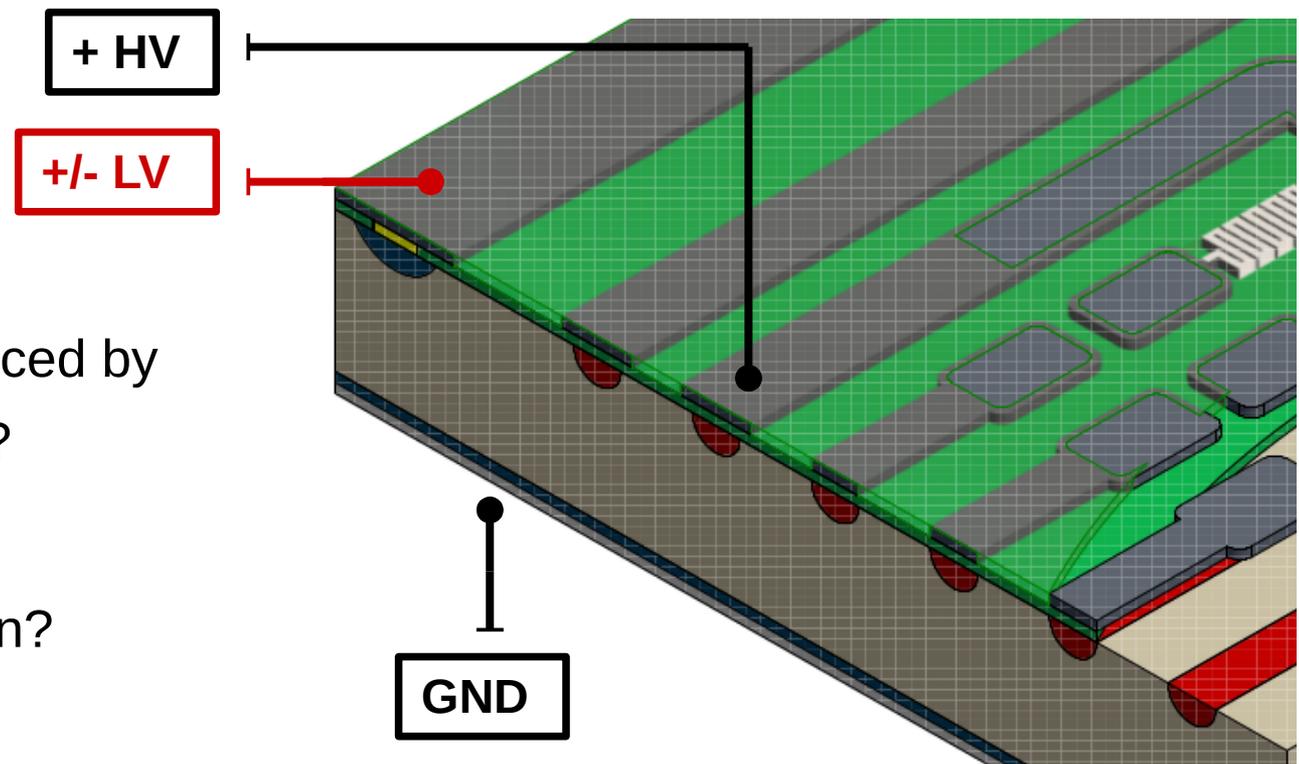
- Charge collection measurements also indicate the voltage drop
  - lower seed signal with FSB



# III. Evaluation of the Sensor Edge's Resistivity

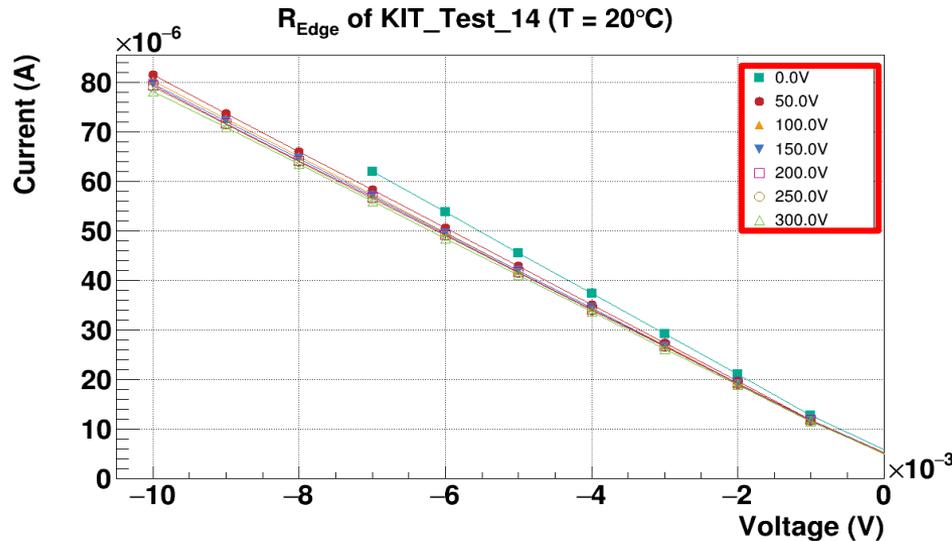
### III. Evaluation of the Sensor Edge's Resistivity

- Systematic studies of edge resistivity (ER) on mini-strip sensors with our probe station setup

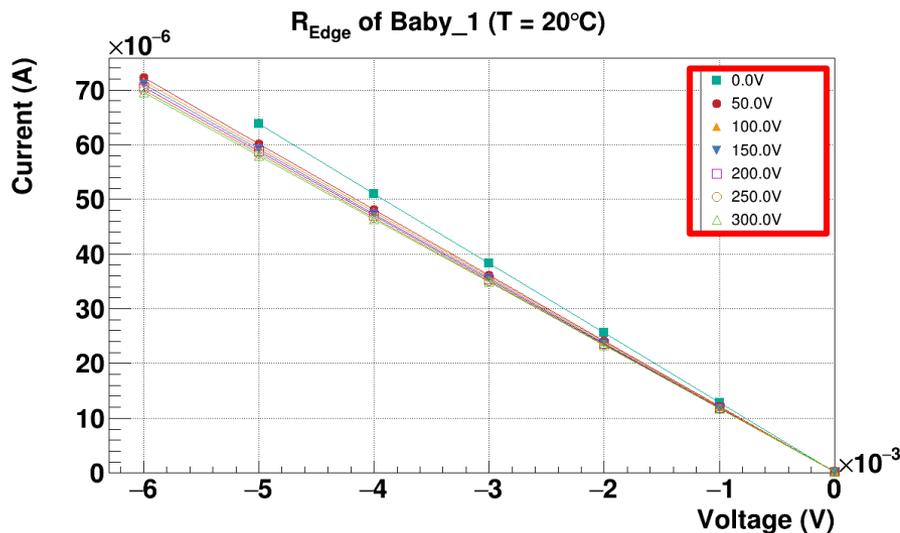


- How is ER influenced by
  - temperature?
  - irradiation?
  - bulk depletion?

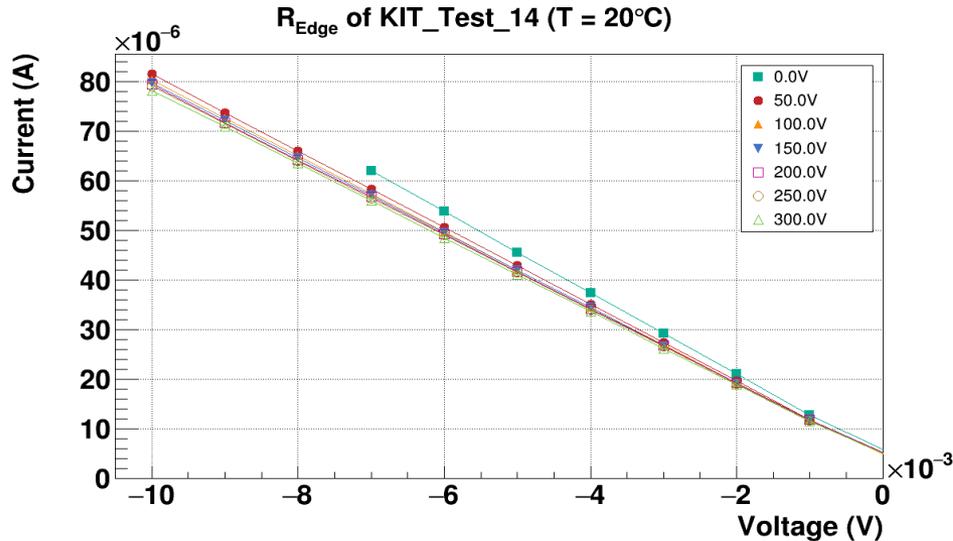
# III. Evaluation of the Sensor Edge's Resistivity



$V_{\text{bias}}$  has no significant impact on  $R_{\text{edge}}$



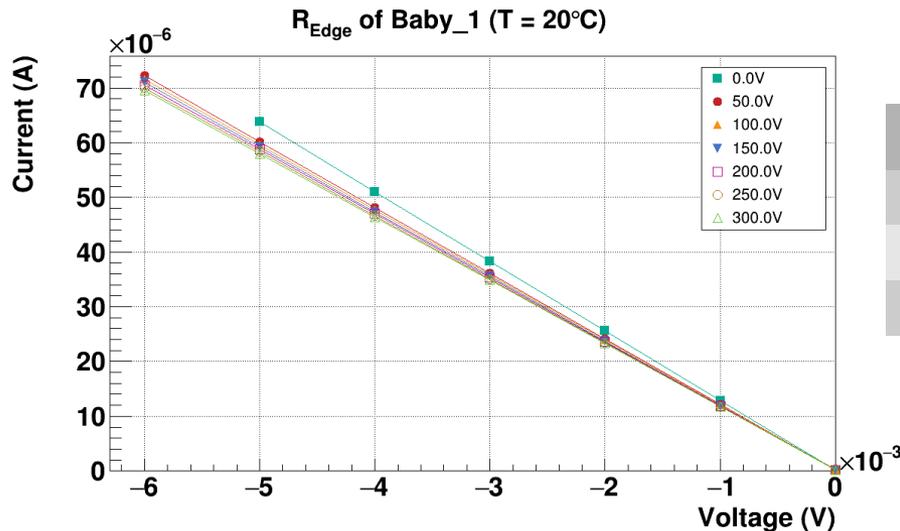
# III. Evaluation of the Sensor Edge's Resistivity



$V_{bias}$  has no significant impact on  $R_{edge}$

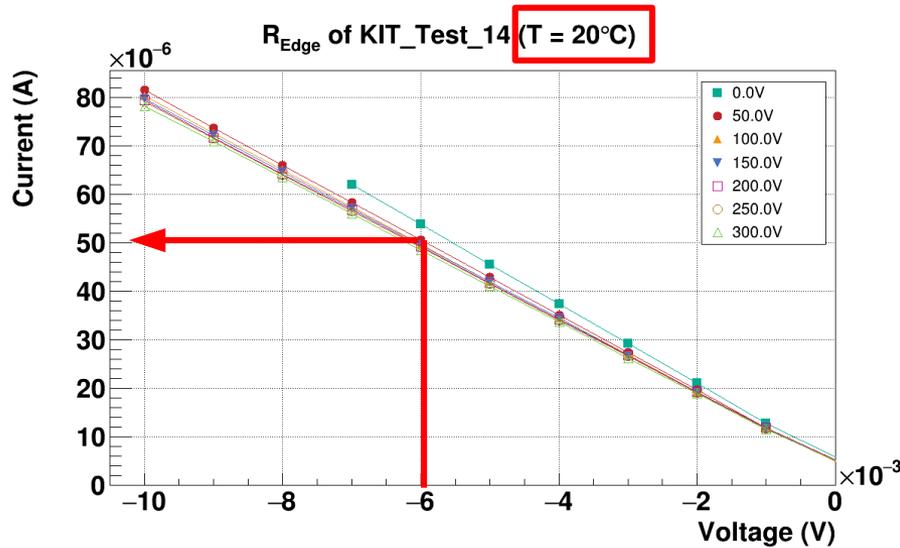
“ $R \sim 1/A_{Per}$ “:

- Resistor formula:  
 $R = \rho \cdot L/A$



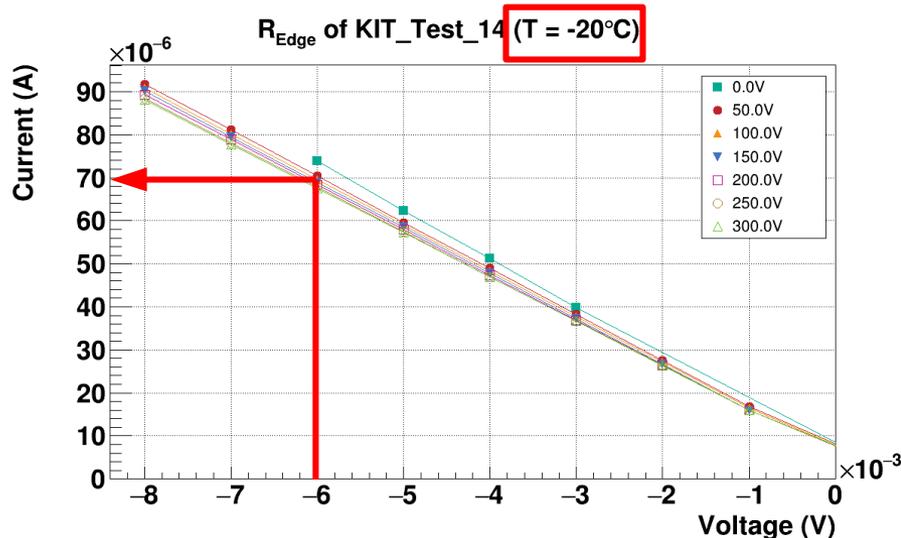
Name	R ( $\Omega$ )	$A_{Per}$ (cm <sup>2</sup> )	L ( $\mu$ m)	$\rho$ ( $\Omega$ cm)
<b>@20°C:</b>				
Baby_1	79	1.209	240	1.1k
KIT_Test_14	124	0.688	240	3.5k

# III. Evaluation of the Sensor Edge's Resistivity

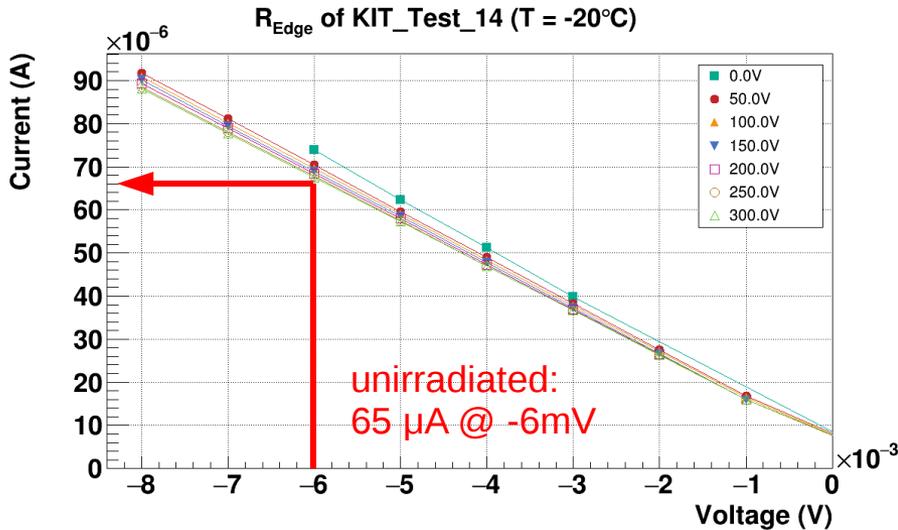


■ Before irradiation:  
 “ $\rho \sim T$ “:

- Resistivity of intrinsic Si:  
 $\rho = [q(n\mu_n + p\mu_p)]^{-1}$
- Carrier mobility of intrinsic Si:  
 $\mu_p \sim T^{-2.3}$ ,  $\mu_n \sim T^{-2.6}$

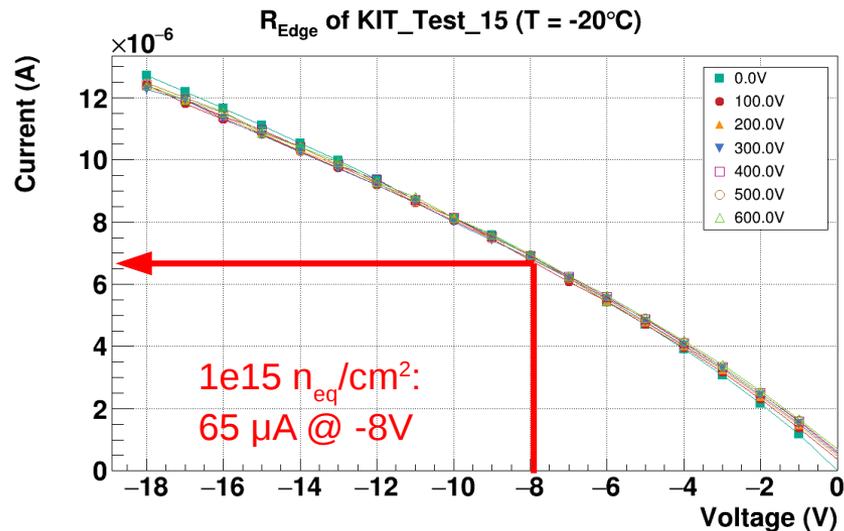


# III. Evaluation of the Sensor Edge's Resistivity



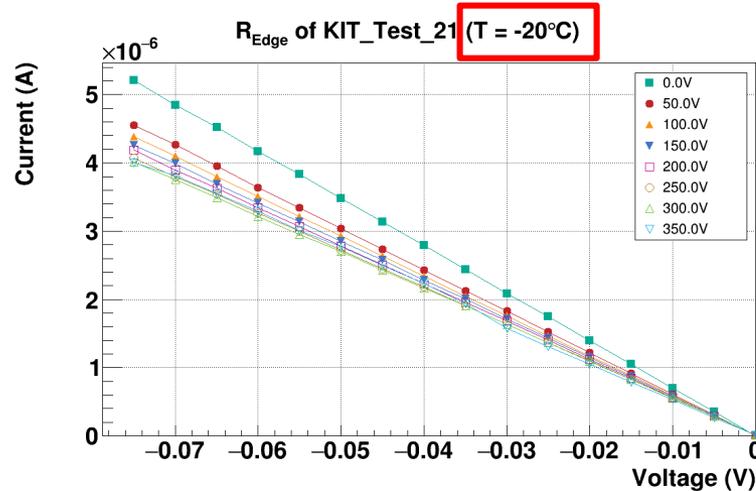
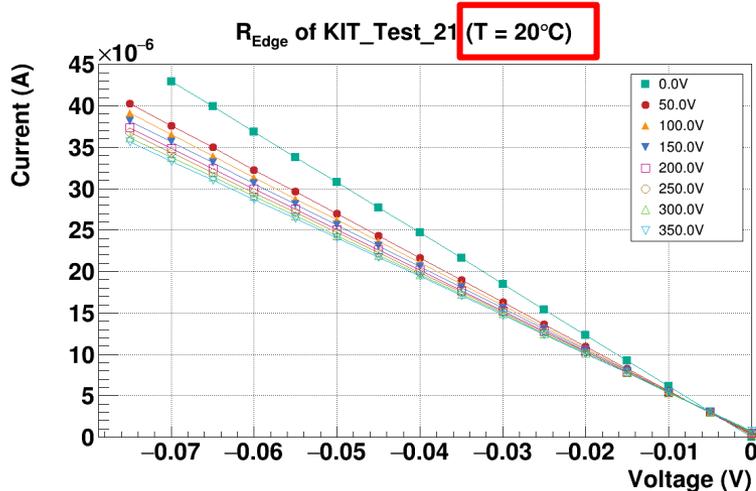
■ “ $\rho \sim \varphi_{\text{eq}}$ ”:

- Space-charge-limited current (SCL current)
- ➔ emerging E-field reduces the current flow after irradiation



Name	$\Phi$ ( $n_{\text{eq}}/\text{cm}^2$ )	R ( $\Omega$ )	$A_{\text{Per}}$ ( $\text{cm}^2$ )
@-20°C:			
KIT_Test_14	-	92	0.621
KIT_Test_15	1e15p	1M	0.621

# III. Evaluation of the Sensor Edge's Resistivity



## ■ After irradiation

“ $\rho \sim 1/T$ “:

- Trapping probability decreases with rising temperature:

$$P(\tau) \sim 1/T \text{ [1]}$$

→ E-field decreases

[1] G. Kramerberger et al. *Effective trapping time of electrons and holes in different silicon materials irradiated with neutrons, protons and pions*. URL: [http://www-f9.ijs.si/~zavrtani/mi\\_02\\_c.pdf](http://www-f9.ijs.si/~zavrtani/mi_02_c.pdf)

# IV. Approximating the Voltage Drop of a 2S Sensor

## IV. Approximating the Voltage Drop for a 2S Sensor

- Most important question: How big is the voltage drop of a 2S sensor?
  - This can be approximated by using
    - the experimentally found resistivities of mini sensors  $\rho_{\text{mini sensor}}$
    - the 2S periphery area  $A_{\text{Per, 2S}} = 3.846 \text{ cm}^2$
    - the 2S leakage current using damage rate damage rate  $\alpha = \Delta I / (V \varphi_{\text{eq}}) = 4 \cdot 10^{-17} \text{ A/cm}$ :
      - $\varphi_{\text{eq}} = 6e14 \text{ n}_{\text{eq}}/\text{cm}^2$
      - $T = -20 \text{ }^\circ\text{C}$
      - 2 weeks annealing @RT
      - $V_{\text{Bias}} = 600 \text{ V}$
- $I = 1.1 \text{ mA}$

## IV. Approximating the Voltage Drop for a 2S Sensor

Name	Fluenz	R ( $\Omega$ )	A <sub>Per</sub> (cm <sup>2</sup> )	L ( $\mu$ m)	$\rho$ ( $\Omega$ cm)	R <sub>2S</sub> ( $\Omega$ )	$\Delta U@1.1$ mA	$\Delta W@1.1$ mA
<b>@20°C:</b>								
KIT_Test_14	-	124	0.621	240	3210	20	<b>0.022</b>	0.00007
KIT_Test_21	1e13p	1630	0.621	240	42198	263	<b>0.290</b>	0.00095
MaPSA_std_9_2	-	694	0.406	200	14097	88	<b>0.097</b>	0.00032
<b>@-20°C:</b>								
KIT_Test_14	-	92	0.621	240	2382	15	<b>0.016</b>	0.00005
KIT_Test_21	1e13p	14415	0.621	240	373183	2328	<b>2.561</b>	0.00841
KIT_Test_16	6e14p	914000	0.621	240	23662089	147630	<b>162.393</b>	0.53294
KIT_Test_15	1e15p	1463210	0.621	240	37880312	236339	<b>259.973</b>	0.85318

Voltage drop and power loss becomes too severe for 2S sensor

# V. Summary

## V. Summary

- Voltage drop becomes significant for high fluences
- Approximated voltage drop for 2S sensor becomes too severe
  - this needs to be experimentally verified!
- We used sensors with standard periphery design
  - there's possible room for improvement
- Even if FSB doesn't meet the requirements for CMS it might be interesting for other detectors
  - LHCb will probably use front-side-biased sensors  
(expected fluence here:  $\sim 1e13 n_{eq}/cm^2 - 1e14 n_{eq}/cm^2$  [2])

[1] A. Abba et al. *Study of prototype sensors for the Upstream Tracker Upgrade*.  
URL: <https://cds.cern.ch/record/2137551/files/LHCb-PUB-2016-007.pdf>

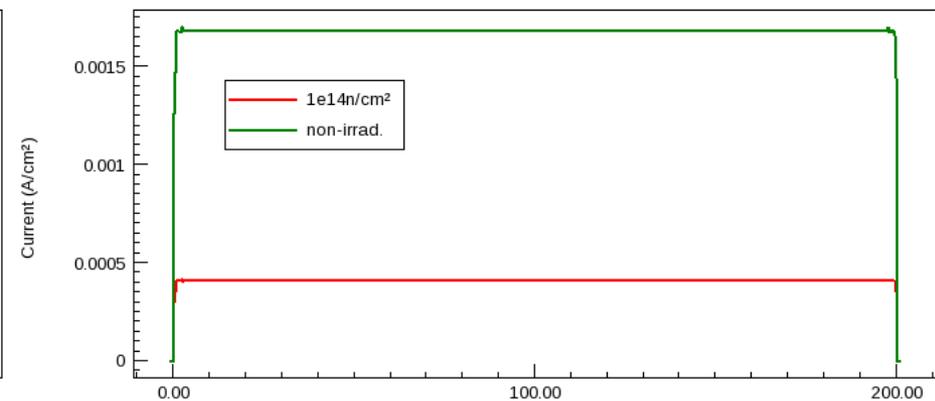
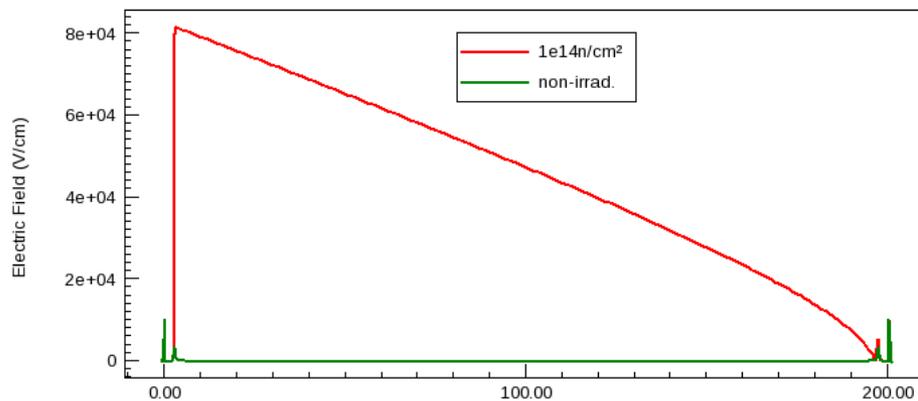
# Backup

# III. Evaluation of the Sensor Edge's Resistivity

Name	$\Phi$ ( $n_{eq}/cm^2$ )	R ( $\Omega$ )	$A_{Per}$ ( $cm^2$ )	L ( $\mu m$ )	$\rho$ ( $\Omega cm$ )
<b>@20°C:</b>					
MaPSA_std_9_2	-	694	0.406	200	14097
KIT_Test_14	-	124	0.621	240	3210
KIT_Test_21	1e13p	1630	0.621	240	42198
<b>@-20°C:</b>					
MaPSA_std_9_2	-	581	0.406	200	11802
KIT_Test_14	-	92	0.621	240	2382
KIT_Test_21	1e13p	14415	0.621	240	373183
KIT_Test_16	6e14p	914000	0.621	240	$23 \cdot 10^6$
KIT_Test_15	1e15p	$1 \cdot 10^6$	0.621	240	$37 \cdot 10^6$
MaPSA_edge500_2_3	1e15p	$2 \cdot 10^6$	0.236	200	$28 \cdot 10^6$
MaPSA_edge350_2_3	1e15p	$4 \cdot 10^6$	0.214	200	$51 \cdot 10^6$

## II. Evaluation of Front-Side-Biased Sensor Parameters

- Simulations of a 200  $\mu\text{m}$  edge region support the results of the experimentally found data
  - an E-field emerges after irradiation that reduces the current flow

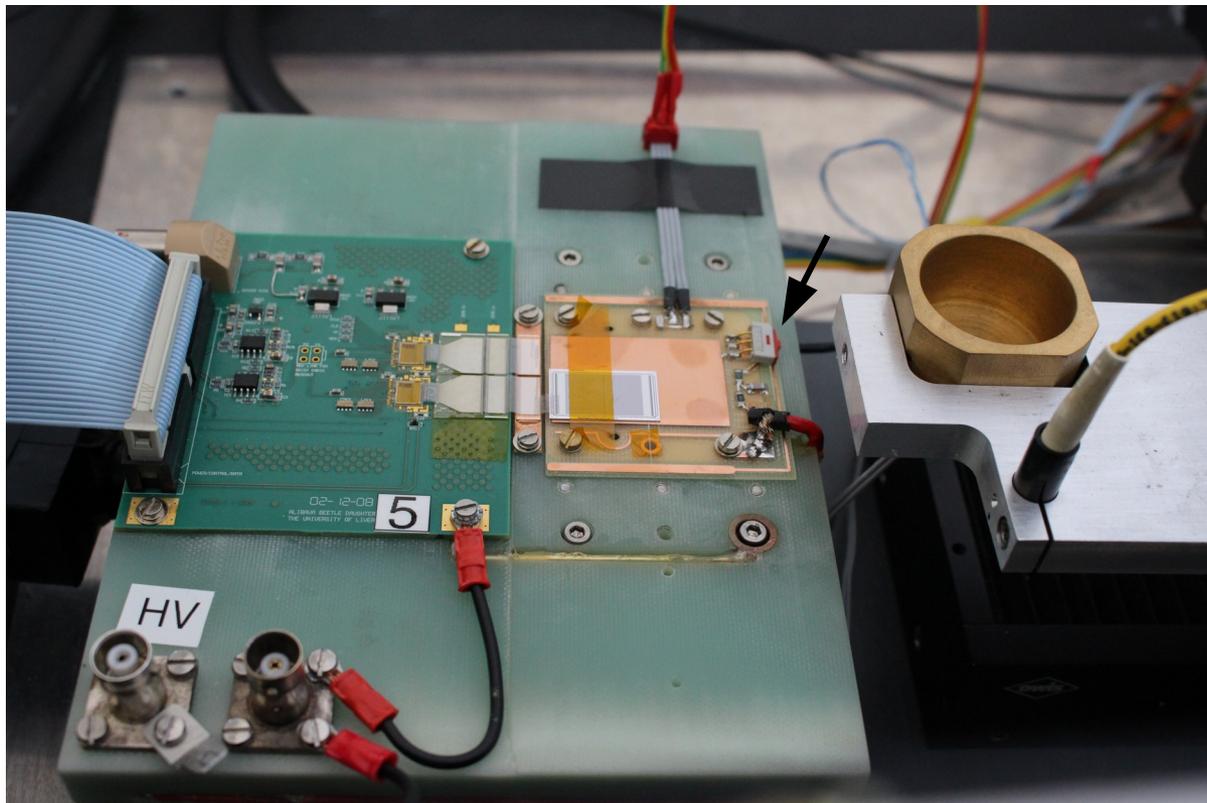


- E-field over  $x$ : shows an emerging E-field after irradiation

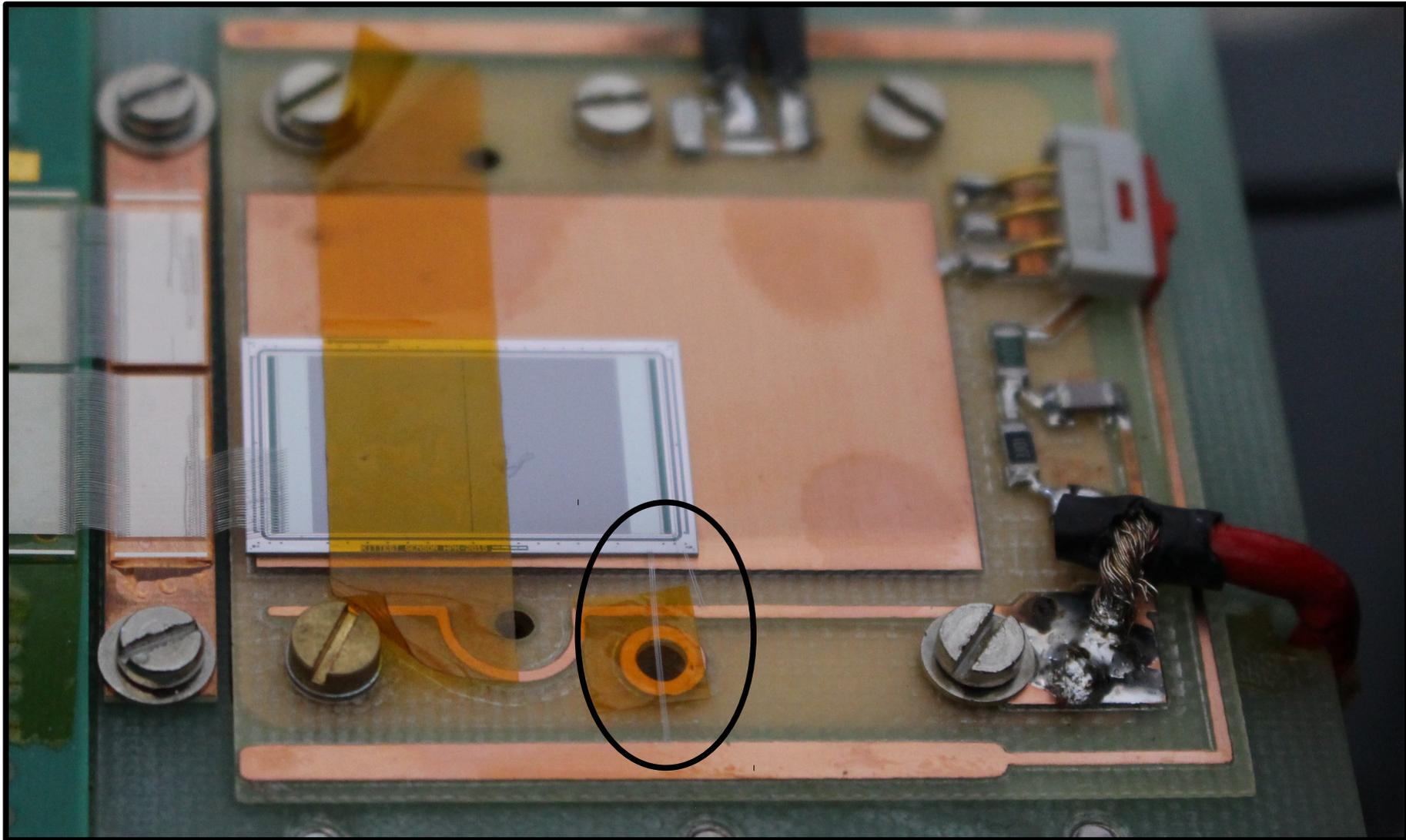
- Current over  $x$ : shows how the current is reduced by  $\sim 70\%$  after irradiation

## II. ALiBaVa Measurements

- Board modulation allows switching back and forth between FSB and BSB while measuring CCE with the ALiBaVa setup

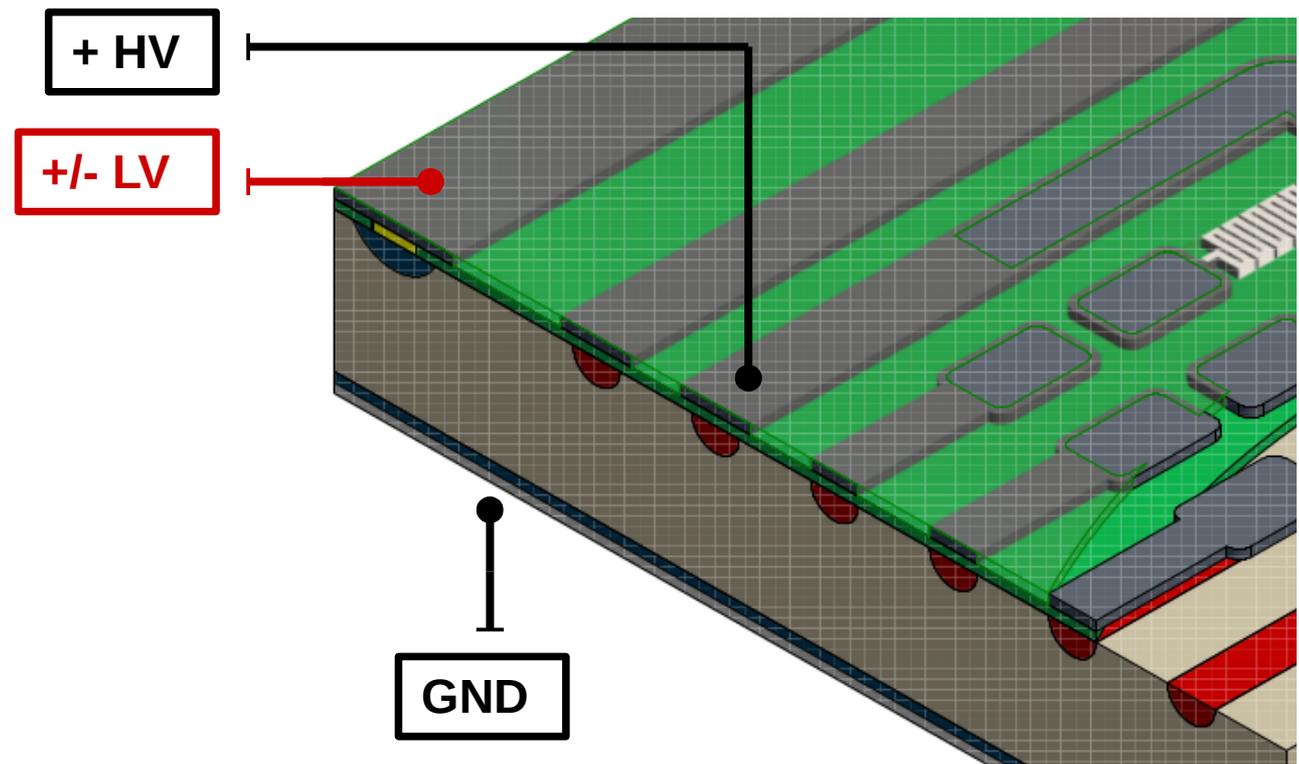


## II. ALiBaVa Measurements: HPK Campaign



## ER Measurements: Basic Idea

- Therefore a new probe station measurement was implemented, which is able to control all those parameters and facilitates the data acquisition



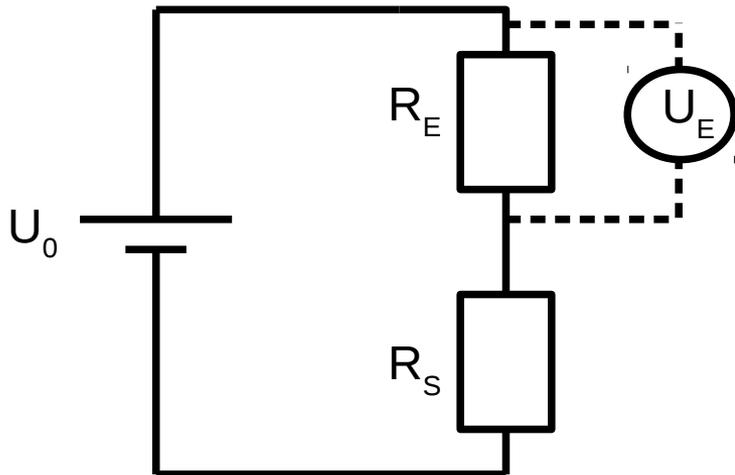
### III. ER Measurements: Basic Idea

■ BSB:  $I_{\text{BSB}} = U_0 / R_S$

■ FSB:  $U_E = I_{\text{FSB}} / R_E$

$$\rightarrow I_{\text{FSB}} = U_0 / (R_S + R_E) = U_0 / (R_S + U_E / I_{\text{FSB}})$$

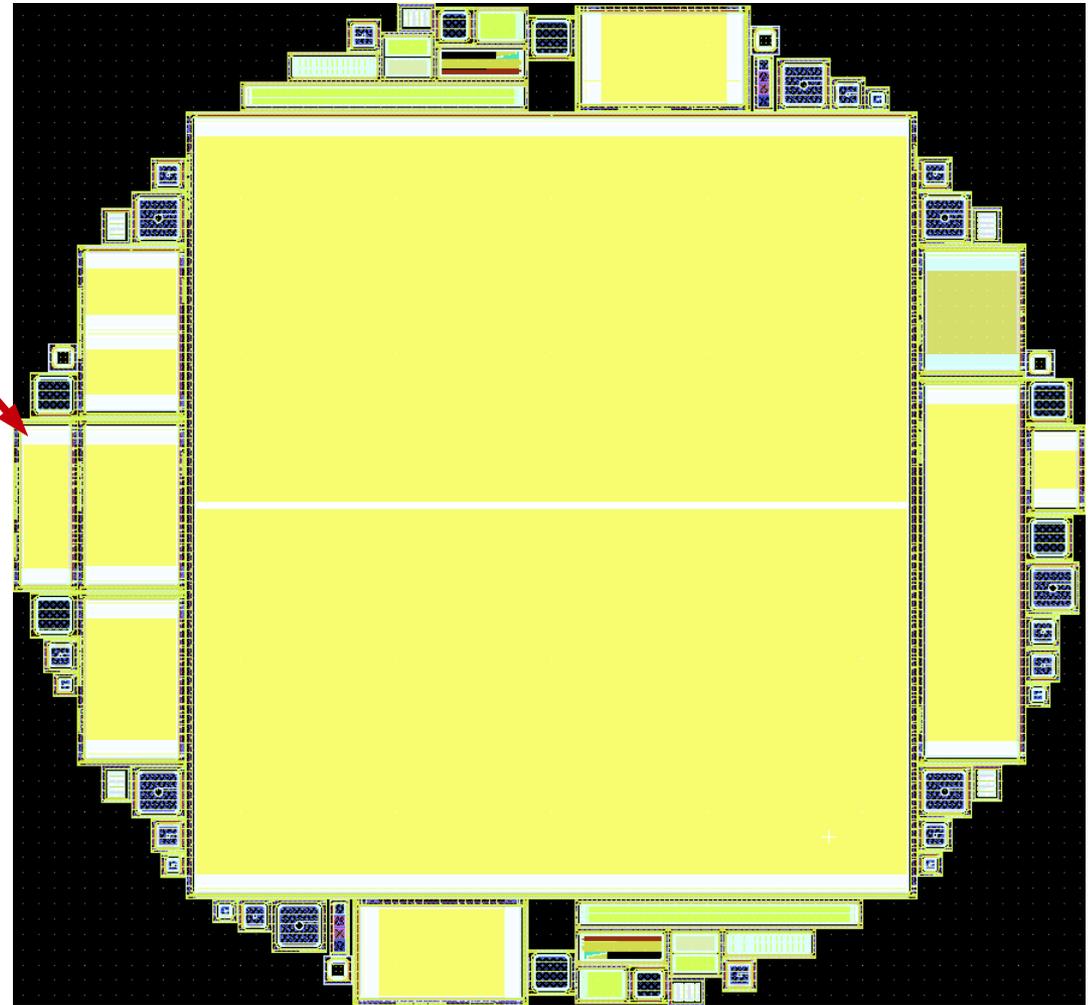
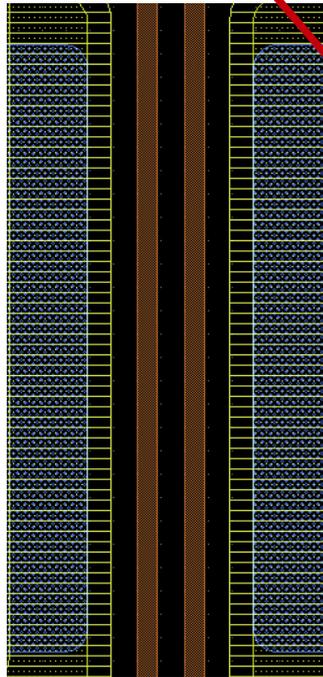
$$\rightarrow U_E = U_0 - I_{\text{FSB}} R_S$$



# I. FZ240dd Sensors: The HPK 2S Wafer

Irradiation

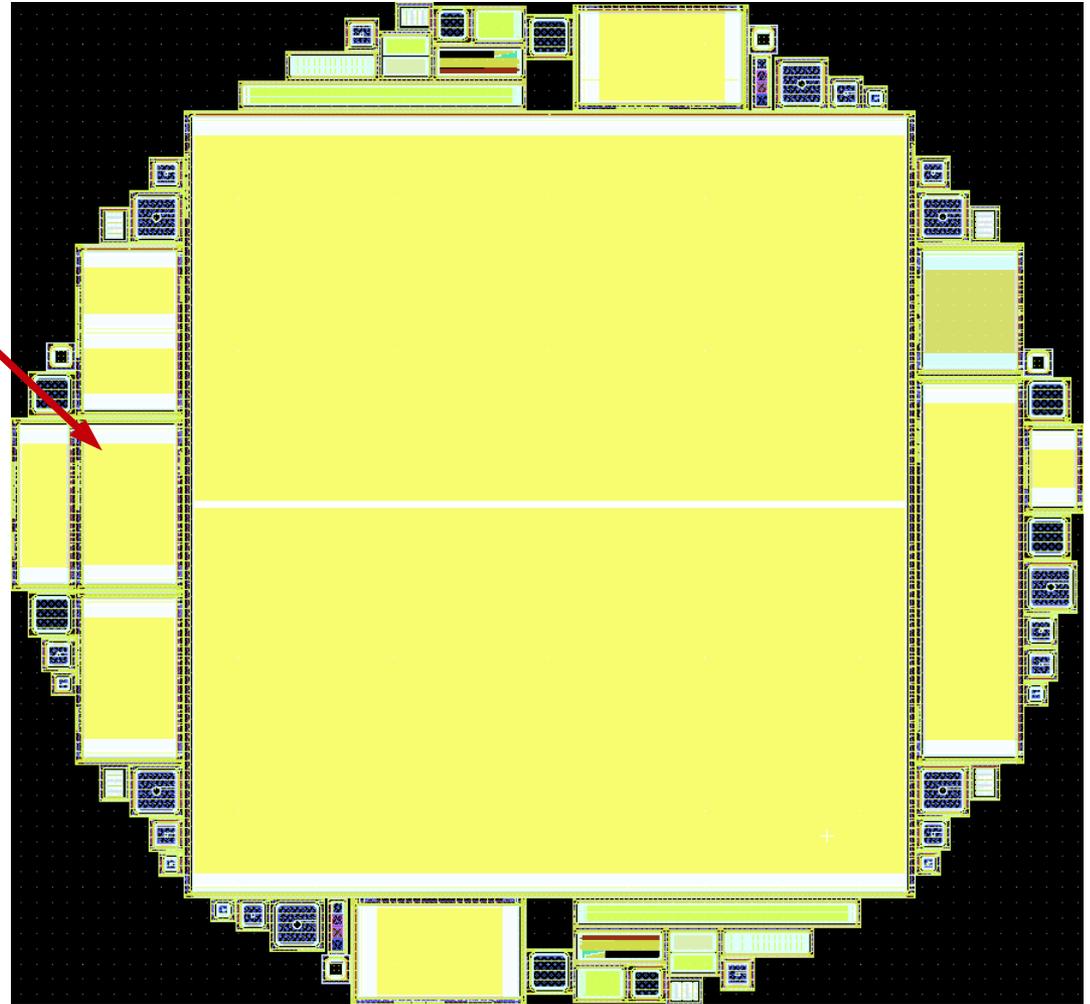
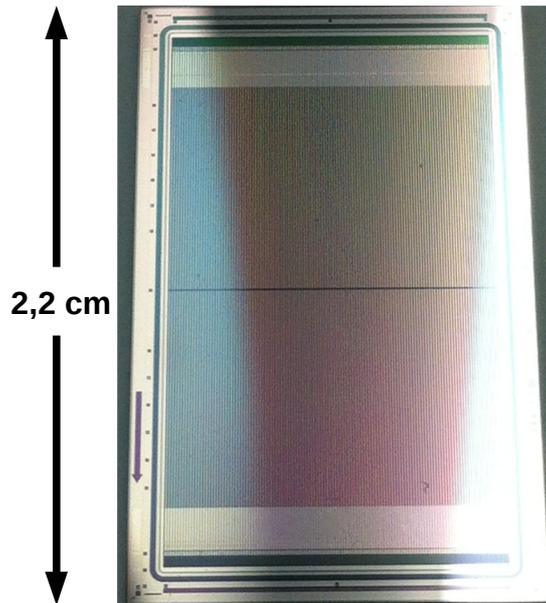
64 strips with p-stop  
isolation



# I. FZ240dd Sensors: The HPK 2S Wafer

## KIT Test

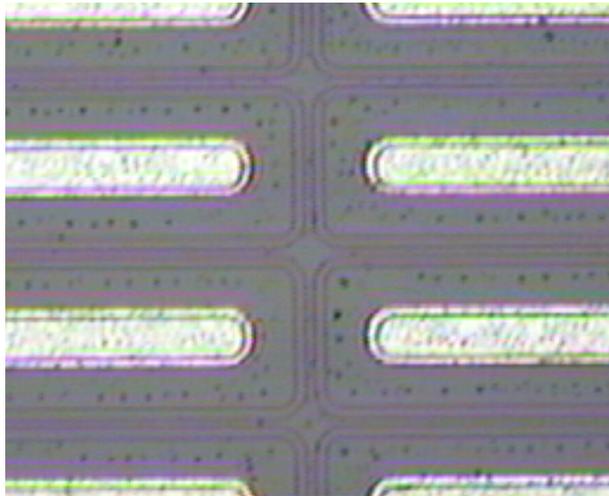
127 segmented or  
respectively 254 strips  
with p-stop isolation



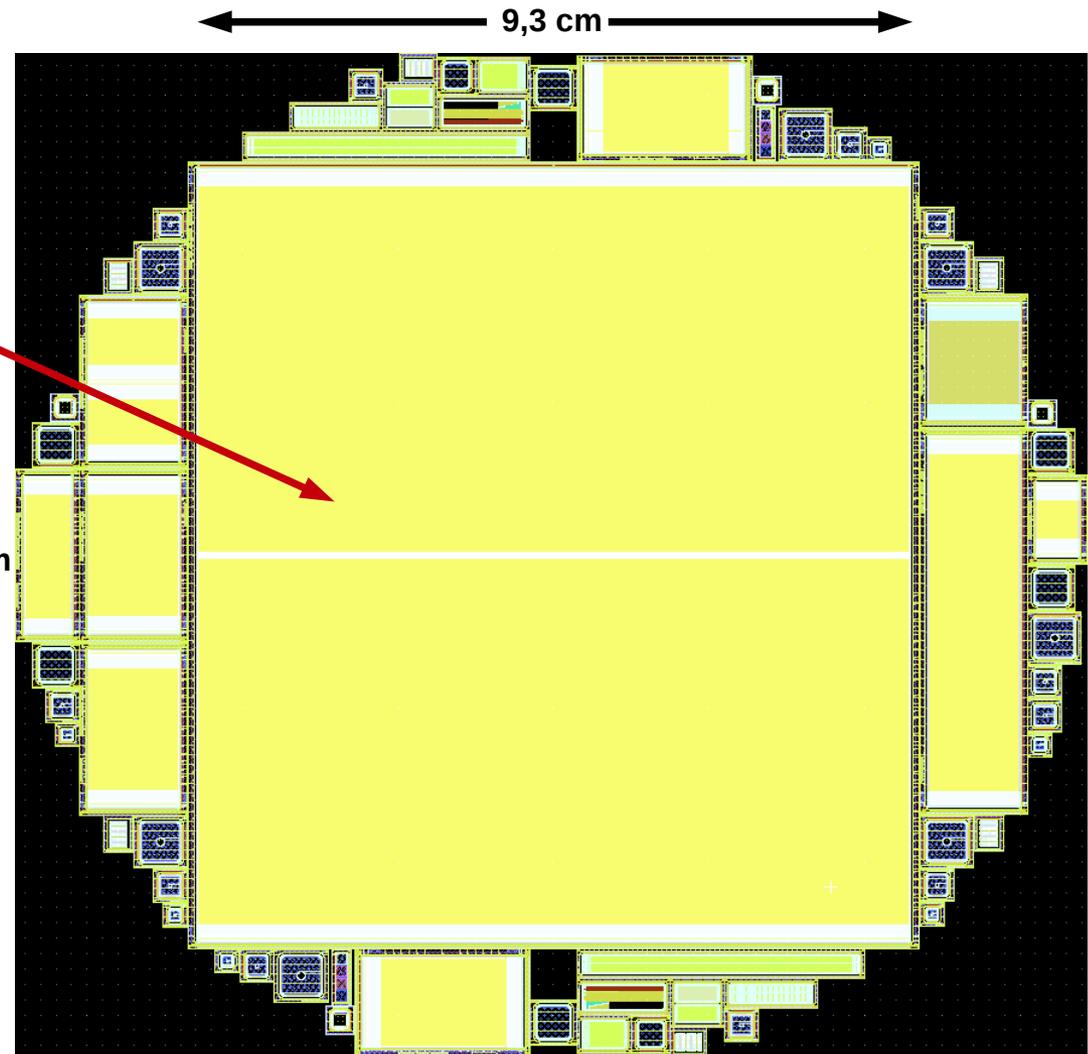
# I. FZ240dd Sensors: The HPK 2S Wafer

## 2S Sensor

1016 segmented  
or respectively  
2032 strips with p-  
stop isolation



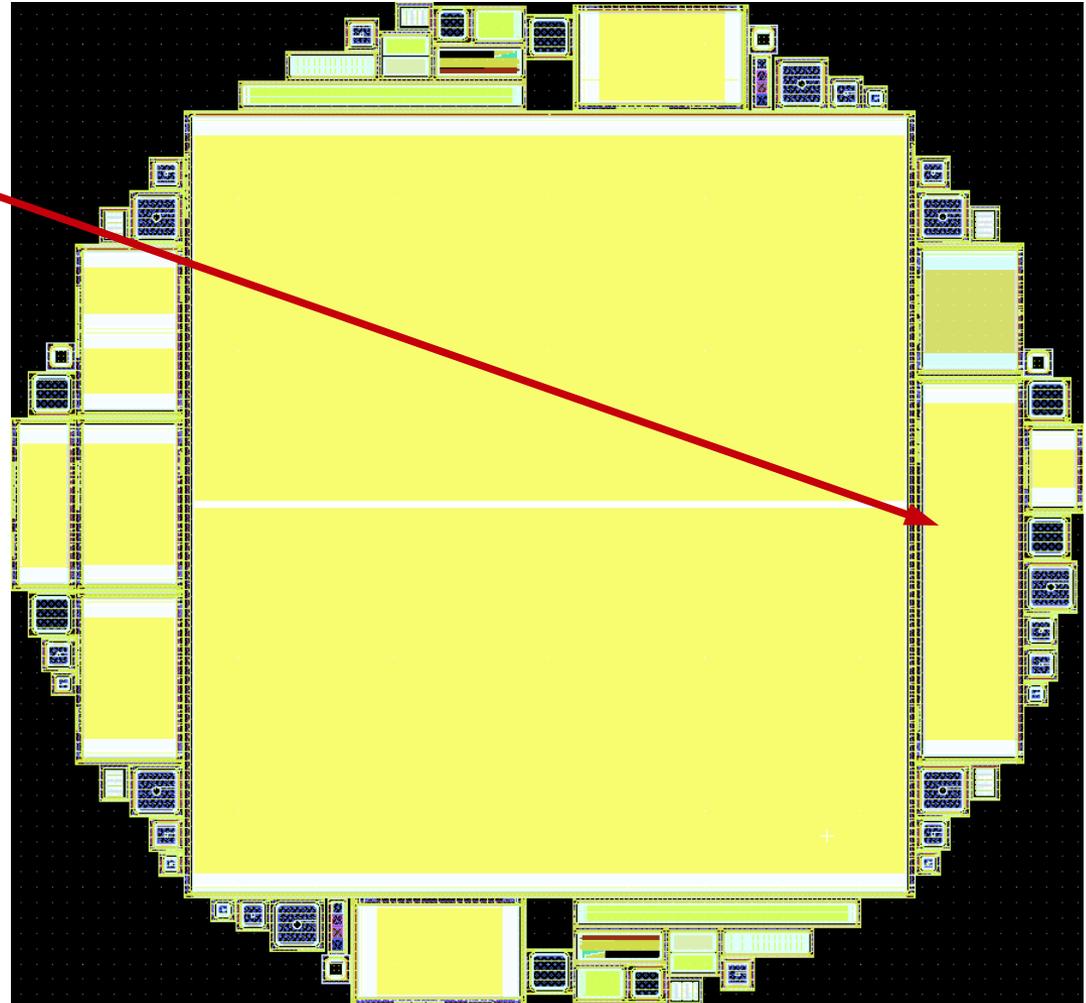
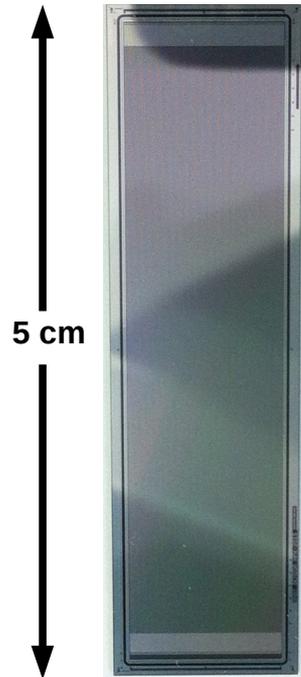
10,2 cm



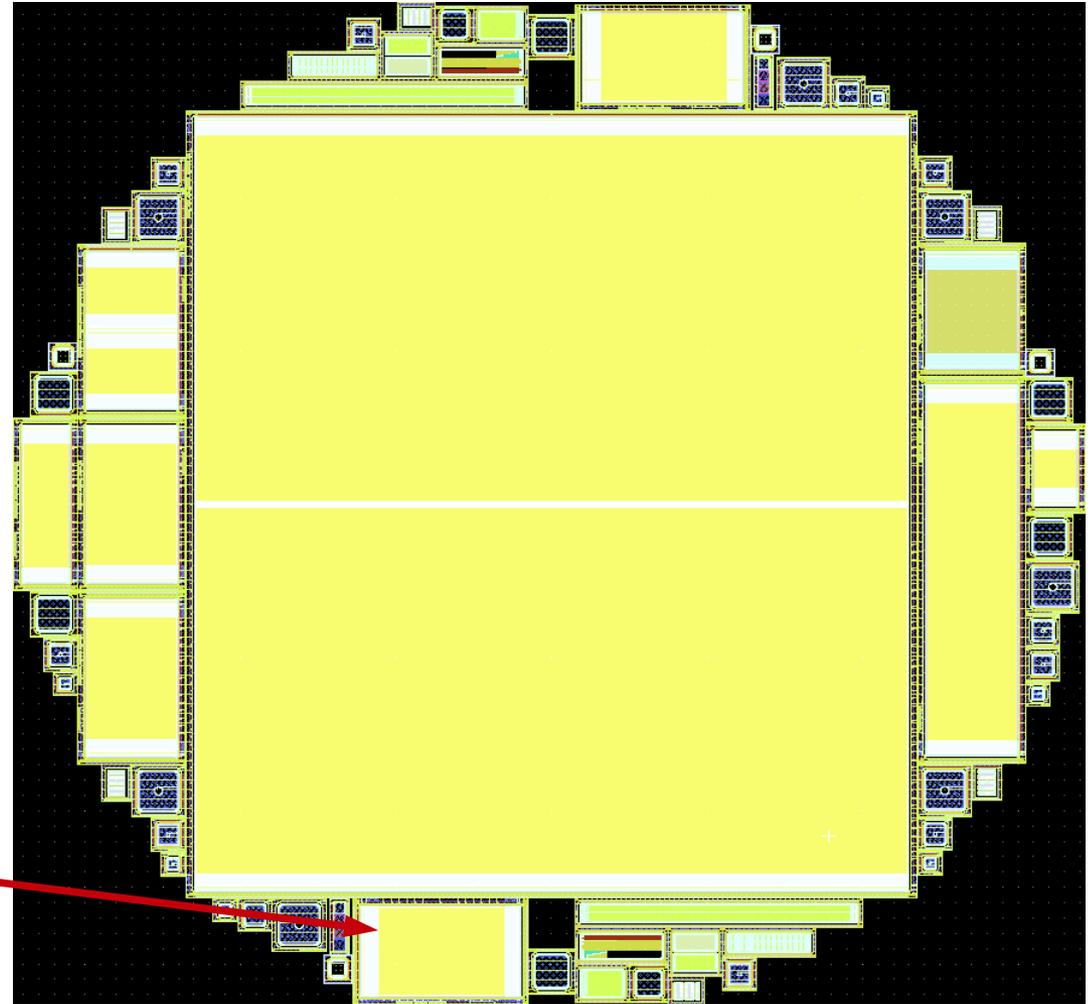
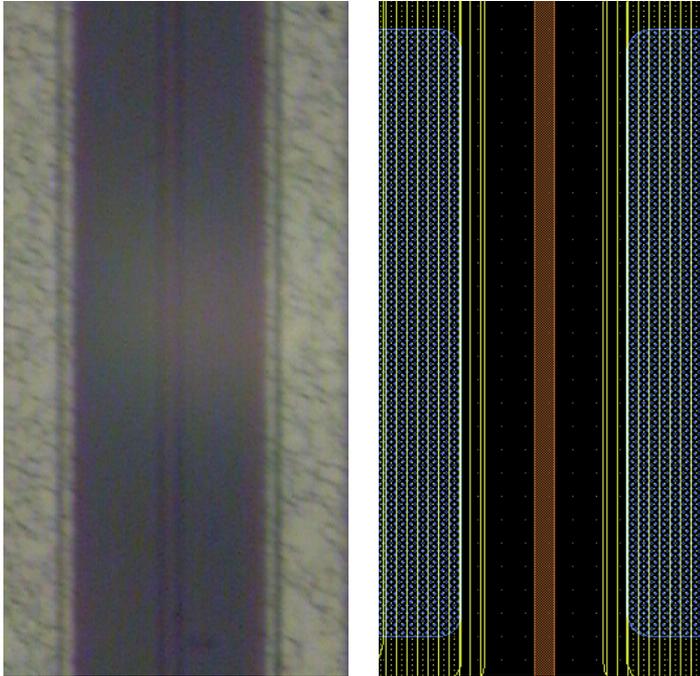
# I. FZ240dd Sensors: The HPK 2S Wafer

## Baby

127 strips with p-stop isolation of almost the same length as the 2S strips



# I. FZ240dd Sensors: The HPK 2S Wafer



PCommon  
127 strips with common  
p-stop isolation